



Correction to: Simulation of abrasive polishing process of single crystal silicon based on molecular dynamics

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The original article contained a mistake.

In the originally published paper, the acknowledgements are wrong. Two funding funds have been repeated (Guizhou University cultivation project (Guida cultivation [2020] No. 10), and Guizhou University cultivation project (Guida cultivation [2020] No. 10)). The acknowledgement is now correctly shown below:

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The original article has been corrected.

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